

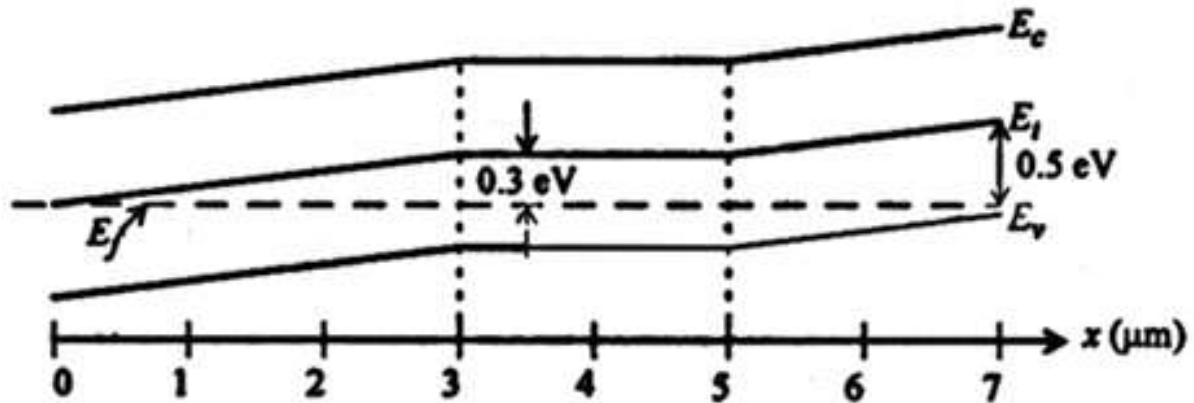
Instructions: (i) Answer All questions. Assume  $T=300\text{K}$  unless specified otherwise.

(ii) Any required data not explicitly given, may be suitably assumed and stated.

(iii) All answers and figures should be written using PEN only.

(iv) Each question should be started from a fresh page. Enclose the final answer in a box.

Q1. The energy band diagram of a silicon sample is shown below.



- Sketch the electrostatic potential inside the semiconductor as function of distance ( $x$ ).
- Sketch the electric field as a function of distance ( $x$ ).
- At  $x=4\ \mu\text{m}$  find the concentration of electrons and holes.
- What is the electron drift current density at  $x = 0\ \mu\text{m}$ . [12]

Q2. Consider an N-type semiconductor bar with equilibrium electron density  $n_0 = 10^{17}\text{ cm}^{-3}$  and intrinsic carrier concentration  $n_i=10^{10}\text{ cm}^{-3}$ . When the sample is illuminated with light, it generates  $10^{18}$  electron-hole pairs/ $\text{cm}^3\text{-sec}$  within the sample with  $\tau_p=\tau_n= 10^{-6}\text{ sec}$ :

- Is the semiconductor in low-level or high-level injection? Explain why?
- Calculate the thermal equilibrium Fermi level with respect to  $E_i$
- Determine  $F_n$  and  $F_p$  with respect to  $E_i$ . Also draw the energy level diagram. [10]

Q3. A certain semiconductor has  $N_C = 10^{19}/\text{cm}^3$ ,  $N_V = 5 \times 10^{18}/\text{cm}^3$ , and  $E_g = 2\text{ eV}$ . If it is doped with  $10^{17}/\text{cm}^3$  donors, calculate the electron, hole and intrinsic carrier concentration at  $900\text{ K}$ . Sketch the simplified band diagram, showing the position of  $E_F$ . Assume that the values of  $N_C$ ,  $N_V$  and  $E_g$  are independent of temperature. [12]

Q4. The total junction capacitance of a one sided silicon pn junction at  $T=300\text{K}$  is measured at  $V_R= 60\text{ mV}$  and found to be  $1.5\text{ pF}$ . The junction area is  $10^{-5}\text{ cm}^2$  and  $V_{bi}= 0.95\text{ V}$ .

- Find the impurity doping concentration of the low-doped side of the junction.
- Find the impurity doping concentration of the higher-doped region. [10]

Q5. An abrupt silicon pn junction at zero bias has electron and hole concentration on p-side and n-side is  $10^{17} \text{ cm}^{-3}$  and  $5 \times 10^{15} \text{ cm}^{-3}$ , respectively at  $T = 300 \text{ K}$ . (a) Calculate the Fermi level on each side of the junction with respect to the intrinsic Fermi level. (b) Sketch the equilibrium energy band diagram for the junction and determine  $V_{bi}$ . Determine the peak-electric field for this junction. [10]

Q6. An Au-n-Si junction with  $N_d = 5 \times 10^{15} \text{ cm}^{-3}$  has a cross sectional area of  $A = 5 \times 10^{-4} \text{ cm}^2$  and is maintained at  $T=300\text{K}$ . Determine (a) barrier height, (b) built-in voltage (c) junction capacitance when  $V_R = 4\text{V}$ . [12]

Q7. Assume that the p+n junction of uniformly doped silicon n-channel JFET at  $T=300 \text{ K}$  has doping concentration of  $N_a=10^{18} \text{ cm}^{-3}$ ,  $N_d= 10^{16} \text{ cm}^{-3}$  and the metallurgical thickness  $a= 0.75 \mu\text{m}$ . Calculate (i) built-in potential, (ii) pinch-off voltage( $V_P$ ) and (iii) What is the effect of built-in potential on pinch-off voltage? [12]

Q8. Consider two p-n silicon junctions at  $T = 300 \text{ K}$  reverse biased at  $V_R = 5 \text{ V}$ . The impurity doping concentrations in pn junction- A are  $N_a = 10^{18}/\text{cm}^3$  and  $N_d = 10^{15}/ \text{cm}^3$  and pn junction- B are  $N_a = 10^{18}/\text{cm}^3$  and  $N_d = 10^{16}/ \text{cm}^3$ . Assuming  $n_i = 1.5 \times 10^{10} \text{ cm}^{-3}$ , calculate the ratio of the following parameters for junction A to junction B:

(a) Depletion Width and (b) Junction Capacitance

(c) In which diode the avalanche mechanism is more significant and why? [12]

-----ALL THE BEST-----

**List of constants:**

$k = 8.62 \times 10^{-5} \text{ eV/K}$

$\epsilon_o = 8.854 \times 10^{-14} \text{ F/cm}$

$q = 1.6 \times 10^{-19} \text{ C}$

$\mu_p (\text{Si}) = 480 \text{ cm}^2/\text{V-s}$

$E_g(\text{Si}) = 1.1 \text{ eV}$

$\chi(\text{Si}) = 4.01 \text{ eV}$

$N_C(\text{Si}) = 2.8 \times 10^{19} \text{ cm}^{-3}$

At  $T=300\text{K}$   $kT=0.0259 \text{ eV}$

$\epsilon (\text{Si}) = 11.8 \epsilon_o$

$n_i (\text{Si}) = 1.5 \times 10^{10} / \text{cm}^3$

$\mu_n (\text{Si}) = 1350 \text{ cm}^2/\text{V-s}$

$\epsilon (\text{SiO}_2) = 3.9 \epsilon_o$

$\phi_m(\text{Au}) = 4.75 \text{ eV}$

$N_V(\text{Si}) = 1.04 \times 10^{19} \text{ cm}^{-3}$ .